

L Number	Hits	Search Text	DB	Time stamp
-	680	exposure adj2 (device or apparatus) same gas	USPAT; US-PGPUB	2003/10/24 09:44
-	184	exposure adj2 (device or apparatus) same gas same pressure	USPAT; US-PGPUB	2003/06/02 14:30
-	790	700/108.ccls. or 702/183,184.ccls.	USPAT; US-PGPUB	2003/06/02 15:07
-	796	700/121,301.ccls.	USPAT; US-PGPUB	2003/06/09 10:30
-	67	exposure adj2 (device or apparatus) same gas same pressure same (semiconductor or wafer)	USPAT; US-PGPUB	2003/06/09 15:09
-	370	716/21.ccls.	USPAT; US-PGPUB	2003/06/09 11:15
-	1110	700/121,301.ccls. or 716/21.ccls.	USPAT; US-PGPUB	2003/10/21 14:53
-	209	(semiconductor or wafer) same exposure adj2 (device or apparatus) and gas same pressure same control	USPAT; US-PGPUB	2004/02/12 09:20
-	59	(semiconductor or wafer) same exposure adj2 (device or apparatus) and gas same pressure same control and (refractive adj2 index)	USPAT; US-PGPUB	2003/06/09 15:14
-	122	(700/121,301.ccls. or 716/21.ccls.) and @pd >= "20030608"	USPAT; US-PGPUB	2004/02/11 15:14
-	92	exposure adj2 (device or apparatus) same helium same nitrogen	USPAT; US-PGPUB	2003/10/23 09:41
-	15	exposure adj2 (device or apparatus) same helium same nitrogen same pressure	USPAT; US-PGPUB	2003/10/21 15:13
-	169	exposure same helium same nitrogen same pressure	USPAT; US-PGPUB	2003/10/23 15:04
-	60	exposure same helium same nitrogen same pressure same (difference or higher)	USPAT; US-PGPUB	2003/10/23 15:05
-	169	exposure same helium same nitrogen same pressure	USPAT; US-PGPUB	2003/10/23 16:03
-	60	exposure same helium same nitrogen same pressure same (difference or higher)	USPAT; US-PGPUB	2003/10/23 15:06
-	109	(exposure same helium same nitrogen same pressure) not (exposure same helium same nitrogen same pressure same (difference or higher))	USPAT; US-PGPUB	2003/10/23 16:03
-	63	helium adj2 nitrogen adj2 pressure	USPAT; US-PGPUB	2003/10/23 16:04
-	119	hydrogen same helium same mix	USPAT; US-PGPUB	2003/10/24 09:51
-	133	nitrogen same helium same mix same pressure	USPAT; US-PGPUB	2003/10/24 09:56
-	5	nitrogen same helium same (prevent adj2 mix\$3) same pressure	USPAT; US-PGPUB	2003/10/24 10:16
-	277	helium adj2 balloon	USPAT; US-PGPUB	2003/10/24 10:16
-	2	helium adj2 balloon adj2 pressure	USPAT; US-PGPUB	2003/10/24 10:16
-	48	helium adj2 balloon same pressure	USPAT; US-PGPUB	2003/10/24 10:26
-	467	decompression adj2 chamber	USPAT; US-PGPUB	2003/10/24 10:26
-	10	decompression adj2 chamber and helium same nitrogen	USPAT; US-PGPUB	2003/10/24 11:04
-	10	decompression adj2 chamber same helium	USPAT; US-PGPUB	2003/10/24 13:45
-	106	(700/121,301.ccls. or 716/21.ccls.) and @pd >= "20031020"	USPAT; US-PGPUB	2004/02/11 15:19
-	125	(semiconductor or wafer) same exposure same nitrogen same helium	USPAT; US-PGPUB	2004/02/12 09:46
-	720	(semiconductor or wafer) and nitrogen same helium same pressure same (high\$2 or difference)	USPAT; US-PGPUB	2004/02/12 10:10
-	124	(semiconductor or wafer) and nitrogen same helium same pressure adj2 (high\$2 or difference)	USPAT; US-PGPUB	2004/02/12 10:58